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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re United States Patent Application of:)
Applicants: Chongying Xu, et al.)
Serial No.: 09/551,018)
Date Filed: April 18, 2000)
Title: SILICON REAGENTS AND LOW TEMPERATURE CVD METHOD OF)
FORMING SILICON-CONTAINING GATE DIELECTRIC MATERIALS)
USING SAME)

Examiner: C. Toomer
Group Art Unit: 1714

CERTIFICATE OF MAILING

I hereby certify that this paper or fee is being deposited pursuant to 37 CFR 1.8
on the date indicated below and is addressed to the Asst. Commissioner of Patents,
Washington, DC 20231

Claudia Dene

August 26, 2002
Date

AMENDMENT AND RESPONSE

Asst. Commissioner for Patents
Washington, D.C. 20231

In response to the Office Action dated April 26, 2002, Applicants respectfully
request entry of the following Amendments and consideration of the subsequent remarks.

IN THE CLAIMS

Please amend claims 1-7 and 9-12, and cancel claims 8 and 13-34 as indicated.

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